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Atty. Docket No.: 3600-328-01		Application No.: 10/042,549					
Applicant: Christopher A. MICHALUK							
Filing Date: January 9, 2002		Group Art Unit: Not Yet Assigned					
<b>U.S. PATENT DOCUMENTS</b>							
Examiner Initial*		Document Number	Date	Name	Class	Sub Class	Filing Date If Appropriate
Ato	1	2,950,185	08/23/60	E.G. Hellier et al.	75	0.5	
Ato	2	3,767,456	10/23/73	Glaski	117	71 M	
Ato	3	3,829,310	08/13/74	T.X. Mahy	75	0.5 BB	
Ato	4	4,149,876	04/17/79	Rerat	75	0.5 BB	
Ato	5	4,684,399	08/04/87	Bergman et al.	75	0.5	
Ato	6	5,234,491	08/10/93	Chang	75	622	
Ato	7	5,242,481	09/07/93	Kumar	75	364	
Ato	8	6,193,821	02/27/01	Zhang	148	668	
Ato	9	2001/0001401	05/24/01	Segal	148	670	
<b>FOREIGN PATENT DOCUMENTS</b>							
		Document Number	Date	Country	Class	Sub Class	Translation Yes or No
Ato	10	WO 00/31310	06/02/00	WIPO	—	—	Yes
<b>OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)</b>							
Ato	Kirk-Othmer, Encyclopedia of Chemical Technology, 3rd Edition, Vol. 22, pp. 541-564, 1983.						
Ato	S.I. Wright, G.T. Gray, and A.D. Rollett, <i>Textural and Microstructural Gradient Effects on the Mechanical Behavior of a Tantalum Plate</i> , <u>Metallurgical and Materials Transactions A</u> , 25A, pp. 1025-1031, 1994.						
Ato	C.A. Michaluk, R.O. Burt, and D.P. Lewis, <i>Tantalum 101: Economics and Technology of Ta Materials</i> , <u>Semiconductor International</u> , Vol. 23, No. 8, pp. 271-278, 2000.						
Ato	C.A. Michaluk, <i>Correlating Discrete Orientation and Grain Size to the Sputter Deposition Properties of Tantalum</i> , <u>Journal of Electronic Materials</u> , Vol. 31, No. 1, pp. 2-9, 2002.						
Examiner				Date Considered		4/22/03	
*Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							
Form PTO 1449				Patent and Trademark Office - U.S. Department of Commerce			



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FORM PTO-1449 (REV 7-80)

Atty. Docket No.  
CPM00029CIP(3600-328-01)

Application No. 10/042,549

## INFORMATION DISCLOSURE STATEMENT

APPLICANT: Christopher A. MICHALUK

Filing Date: January 9, 2002

Group Art Unit: 1742

## U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB-CLASS	FILING DATE, IF APPROPRIATE
Alo	3,497,402	2/24/70	Douglass et al.	148	11.5	
Alo	4,844,746	7/4/89	Hormann et al.	148	2	

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DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB-CLASS	TRANSLATION YES NO
Alo WO 01/96620	12/20/01	WIPO	C22B		
Alo WO 99/61670	12/2/99	WIPO	C22B	34/24	
Alo WO 99/66100	12/23/99	WIPO	C23C	14/34	

## OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

Alo	G. I. Friedman, "Grain Size Refinement in a Tantalum Ingot", Metallurgical Transactions., vol. 2, January 1971(1971-01), pages 337-341, XP002227180 METALLURGICAL SOCIETY OF AIME. NEW YORK., US. Page 337, column 1, line 1-page 340, column 2, line 28; table 4.
Alo	S. R. Lampman et al., "Metals Handbook, Vol 2", 1990 ASM INTERNATIONAL, Ohio, US XP002227181, "Niobium", Gerardi. page 565-574.
Alo	International Search Report for PCT/US02/23640, January 23, 2003

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DATE CONSIDERED

4/22/03

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